

FORM PTO-1449
(REV. 7-80)U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICEATTY. DOCKET NO.
26860/33:43 DAPPLICATION NO.
08/659,140

Ed Copy
of IDS
of 10/28/97
Paper #3

INFORMATION DISCLOSURE CITATION
 (Use several sheets if necessary)

APPLICANT
Yunlong Sun and Ed SwensonFILING DATE
September 2, 1997GROUP
1700

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER							DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
GSE	AA	5	6	1	1	9	4	6	03/97	Leong et al.	219	121.68	
GSE	AB	5	5	6	9	3	9	8	10/29/96	Sun et al.	219	121.68	
GSE	AC	5	4	7	3	6	2	4	12/05/95	Sun	372	69	
GSE	AD	5	4	2	0	5	1	5	05/30/95	Uhling et al.	324	601	
GSE	AE	5	2	9	6	6	7	4	03/22/94	Praschek et al.	219	121.69	09/18/92
GSE	AF	5	2	6	5	1	1	4	11/23/93	Sun et al.	372	69	
GSE	AG	5	2	6	0	9	6	3	11/09/93	Baird et al.	372	95	
GSE	AH	5	0	9	6	8	5	0	03/17/92	Lippitt, III	437	173	
GSE	AI	5	0	5	7	6	6	4	10/15/91	Johnson et al.	219	121.69	
GSE	AJ	4	9	8	7	2	8	6	01/22/91	Allen	219	121.68	
GSE	AK	4	9	7	0	3	6	9	11/13/90	Yamazaki et al.	219	121.69	
GSE	AL	4	7	9	2	7	7	9	12/20/88	Pond et al.	338	195	

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
GSE	AM	0 6 1 8 2	03/17/94	PCT	H01S	3/09		
GSE	AN	2 1 0 3 8 8 4	02/23/83	UK	H01C	17/24		

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)

GSE	AO	Dow et al., "Reducing Post-Trim Drift of Thin-Film Resistors by Optimizing YAG Laser Output Characteristics," <u>IEEE Transactions on Components, Hybrids and Mfg. Technology</u> , Vol. Ch-1, No. 4, Dec 1978, pp 392-397
		Gillespie, et al. <u>Applied Optics</u> , Vol. IV, pp 1488 (1985)
GSE	AQ	Jellison, Jr., G.E. et al., "Optical Properties of Heavily Doped Silicon Between 1.5 and 4.1 eV," <u>PHYSICAL REVIEW LETTERS</u> , Vol. 46, No. 21., (May 1981), pub. by The American Physical Society, pp. 1414-1417
		Chih-Youan Lu et al., <u>IEEE, Transactions on Electron Devices</u> , Vol. 36, No. 6, pp 1056-1061 (6/89)

EXAMINER	Geoffrey S. Evans	DATE CONSIDERED
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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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GSE	AA	4	7	9	1	6	3	1	12/03/88	Baumert et al.	372	22	
GSE	AB	4	7	6	1	7	8	6	08/02/88	Baer	372	10	
GSE	AC	4	7	0	8	7	4	7	11/24/87	O'Mara, Jr.	437	19	
GSE	AD	4	7	0	5	6	9	8	11/10/87	Van Dine	427	53.1	
GSE	AE	4	3	9	9	3	4	5	08/16/83	Lapham et al.	219	121	
GSE	AF	4	2	8	8	7	7	6	09/08/81	Holmes	338	308	
GSE	AG	4	1	8	2	0	2	4	01/08/80	Cometta	29	571	
	AH												
	AI												
	AJ												
	AK												

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		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
	AL							
	AM							
	AN							

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)

GSE	AO	Michael J. Mueller, "Functional laser trimming of thin film resistors on silicon ICs," SPIE, Vol. 611,
		Laser Processing of Semiconductors and Hybrids (1986), pp. 70-83.
GSE	AP	SPIE, Vol. 611, Laser Processing of Semiconductors and Hybrids (1986), pp 12-13.
GSE	AQ	R. H. Wagner, "Functional Laser Trimming an Overview," PROCEEDINGS OF SPIE - THE INTERNATIONAL
		SOCIETY FOR OPTICAL ENGINEERING, Vol. 611, 21-22 January 1986, Los Angeles, pp 8-17.
GSE	AR	Weber, "Handbook of Laser Science and Technology," <u>Optical Materials</u> : Part II, CRC Press (10/86)

EXAMINER

Geoffrey S. Evans

DATE CONSIDERED
June 4, 1998

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